

**AMENDMENTS TO THE CLAIMS:**

1. (Previously Presented) An apparatus for holding a substrate, said apparatus comprising:  
a pocket adapted to hold said substrate, wherein said pocket comprises an inner edge and a lower surface;  
a plurality of projections extending radially inward from said inner edge;  
an opening in said lower surface; and  
a pin disposed in said opening, said pin being configured for lifting said substrate from said pocket;  
wherein said projections have a beveled edge, such that an acute angle greater than 80 degrees occurs between said lower surface and said beveled edge, and  
wherein said projections reduce an area of contact between said inner edge and said substrate.
2. (Previously Presented) The apparatus of claim 1, wherein said apparatus comprises a susceptor for holding said substrate.
3. (Original) The apparatus of claim 1, wherein said projections have a "C" shape.
4. (Original) The apparatus of claim 1, wherein said projections maintain a gap between a sidewall of said substrate and said inner edge.
5. (Previously Presented) The apparatus of claim 1, wherein said acute angle comprises an angle not greater than 85 degrees.

6. (Original) The apparatus of claim 1, wherein said projections prevent said substrate from moving within said pocket.
7. (Previously Presented) An apparatus for holding a substrate, said apparatus comprising:  
a pocket adapted to hold said substrate, wherein said pocket comprises an inner edge and a lower surface;  
a plurality of projections extending radially inward from said inner edge; and  
an opening in said lower surface;  
wherein said projections have a beveled edge, and  
wherein an acute angle greater than 80 degrees occurs between said lower surface and said beveled edge.
8. (Canceled).
9. (Original) The apparatus in claim 7, wherein said projections reduce an area of contact between said inner edge and said substrate.
10. (Previously Presented) The apparatus of claim 7, wherein said apparatus comprises a susceptor for holding said substrate.
11. (Original) The apparatus of claim 7, wherein said projections have a "C" shape.

12. (Original) The apparatus of claim 7, wherein said projections maintain a gap between a sidewall of said substrate and said inner edge.
13. (Currently Amended) The apparatus of claim [[8]] 7, wherein said acute angle comprises an angle not greater than 85 degrees.
14. (Original) The apparatus of claim 7, wherein said projections prevent said substrate from moving within said pocket.
15. (Previously Presented) A susceptor for holding a wafer, said susceptor comprising:  
a pocket adapted to hold said wafer, wherein said pocket comprises an inner edge and a lower surface;  
a plurality of projections extending radially inward from said inner edge; and  
a device positioned below said pocket, said device being configured for lifting said wafer from said pocket;  
wherein said projections have a beveled edge, and  
wherein an acute angle greater than 80 degrees occurs between said lower surface and said beveled edge.
16. (Canceled).
17. (Previously Presented) The susceptor of claim 16, wherein said acute angle is not greater than 85 degrees.

18. (Original) The susceptor of claim 17, wherein said projections have a "C" shape.
19. (New) The apparatus according to claim 1, wherein said acute angle is complimented by a complimentary angle, said complimentary angle comprises a range between 5 and 10 degrees.